	Application No.	Applicant(s)
	10/614,529	ROLFSON, J. BRETT
Notice of Allowability	Examiner	Art Unit
	Roberts Culbert	1763
The MAILING DATE of this communication appe All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this app or other appropriate communication IGHTS. This application is subject to	olication. If not included will be mailed in due course. <b>THIS</b>
1. A This communication is responsive to the response filed 5/1	<u>18/05</u> .	
2. ☑ The allowed claim(s) is/are <u>1-56 and 59-110</u> .		
3. $igotimes$ The drawings filed on <u>07 July 2003</u> are accepted by the Ex	aminer.	
<ul> <li>4. Acknowledgment is made of a claim for foreign priority una)</li> <li>All b) Some* c) None of the:</li> <li>1. Certified copies of the priority documents have</li> <li>2. Certified copies of the priority documents have</li> <li>3. Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)).</li> <li>* Certified copies not received:</li> </ul>	been received. been received in Application No	
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		complying with the requirements
<ol> <li>A SUBSTITUTE OATH OR DECLARATION must be submi INFORMAL PATENT APPLICATION (PTO-152) which give</li> </ol>		
<ol> <li>CORRECTED DRAWINGS (as "replacement sheets") mus</li> <li>(a) ☐ including changes required by the Notice of Draftspers</li> <li>1) ☐ hereto or 2) ☐ to Paper No./Mail Date</li> <li>(b) ☐ including changes required by the attached Examiner's Paper No./Mail Date</li> </ol>	on's Patent Drawing Review ( PTO-9	ffice action of
Identifying indicia such as the application number (see 37 CFR 1. each sheet. Replacement sheet(s) should be labeled as such in the	84(c)) should be written on the drawin ne header according to 37 CFR 1.121(d	gs in the front (not the back) of l).
<ol> <li>DEPOSIT OF and/or INFORMATION about the depose attached Examiner's comment regarding REQUIREMENT I</li> </ol>	SIT OF BIOLOGICAL MATERIAL IN FOR THE DEPOSIT OF BIOLOGICA	nust be submitted. Note the AL MATERIAL.
Attachment(s) 1. ⊠ Notice of References Cited (PTO-892)	5. ☐ Notice of Informal Pa	atent Application (PTO-152)
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6. 🔲 Interview Summary (	(PTO-413),
3. 🖂 Information Disclosure Statements (PTO-1449 or PTO/SB/0	Paper No./Mail Date 8), 7. ⊠ Examiner's Amendm	
Paper No./Mail Date <u>1/7/04</u> 4. ☐ Examiner's Comment Regarding Requirement for Deposit	8. 🛛 Examiner's Statemer	nt of Reasons for Allowance
of Biological Material	9.  Other	
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## **EXAMINER'S AMENDMENT**

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

The application has been amended as follows:

Cancel Claims 57, 58, 111 and 112.

Rejoin Claims 21-56 and 59-110.

## Election/Restrictions

This application is in condition for allowance except for the presence of claims 57, 58, 111, and 112 to an invention non-elected without traverse in the reply filed 5/18/05. Accordingly, claims 57, 58, 111, and 112 been cancelled.

## Response to Arguments

Applicant's arguments regarding the rejection under Process claims 21-56 and 59-110 have been fully examined and are hereby rejoined.

## Allowable Subject Matter

Claims 1-56 and 59-110 are allowed.

The following is an examiner's statement of reasons for allowance: The prior art of record fails to teach or render obvious a method of making a photomask comprising: providing a work-piece comprising a substrate having atop surface, a bottom surface opposite to the top surface and an edge connecting the top surface and the bottom surface, the edge defining a periphery of the substrate, wherein a layer of chrome superimposes the top surface and a layer of a photoresist material superimposes the chrome layer; selectively removing a photoresist material from portions of the work-piece adjacent to the periphery to expose the chrome layer while leaving at least one tab of photoresist material covering the chrome layer adjacent to the periphery; removing the exposed chrome layers removing the tab of

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photoresist material, or removing at least one tab if more than one tab is present and removing the

exposed chrome layer as recited in the context of the claims.

The references made of record and not relied upon are considered pertinent to applicant's

disclosure. U.S. Patent 6,830,853 B1 to Tzu et al. teaches a method of etching a chrome mask. U.S.

Patent Application Publication U.S. 2005/0032003 to Lin teaches a method of forming a photomask by

etching a chrome layer using a photoresist. Japanese Patent JP 05289309A to Masahiro teaches a

method of patterning a chromium mask using an electron beam.

Any comments considered necessary by applicant must be submitted no later than the payment

of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such

submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should

be directed to Roberts Culbert whose telephone number is (571) 272-1433. The examiner can normally

be reached on Monday-Friday (8:30-5:00).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor,

Parviz Hassanzadeh can be reached on (571) 272-1435. The fax phone number for the organization

where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application

Information Retrieval (PAIR) system. Status information for published applications may be obtained from

either Private PAIR or Public PAIR. Status information for unpublished applications is available through

Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should

you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC)

at 866-217-9197 (toll-free).

R. Culbert

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